

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	697	electroplating near8 (conc\$6 or (spacing with (anode or cathode)))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:23
2	BRS	L2	524	1 and (@ad<20010719)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:23
3	BRS	L4	1216	electroplat\$6 near8 (concentration or (spacing with (anode or cathode)))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:24
4	BRS	L5	944	4 and (@ad<20010719)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:25
5	BRS	L6	641	5 and (change or changed or changing or revise or revising or revised or alter or altering or control or controlled or controlling)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:26

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L7	416	6 and (Cu or copper)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/28 14:26

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L3	1217	electroplat\$6 near8 (concentration or (spacing with (anode or cathode)))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:35
2	BRS	L4	944	(electroplat\$6 near8 (concentration or (spacing with (anode or cathode)))) and (@ad<20010719)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:35
3	BRS	L5	641	((electroplat\$6 near8 (concentration or (spacing with (anode or cathode)))) and (@ad<20010719)) and (change or changed or changing or revise or revising or revised or alter or altering or control or controlled or controlling)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:35
4	BRS	L1	697	electroplating near8 (conc\$6 or (spacing with (anode or cathode)))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:36
5	BRS	L2	524	(electroplating near8 (conc\$6 or (spacing with (anode or cathode)))) and (@ad<20010719)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:36

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L6	416	((electroplat\$6 near8 (concentration or (spacing with (anode or cathode)))) and (@ad<20010719)) and (change or changed or changing or revise or revising or revised or alter or altering or control or controlled or controlling)) and (Cu or copper)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 09:49
7	IS&R	L8	2	("6685814").PN.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 10:20
8	BRS	L9	3	(electroplate or electroplating or electroplated) with concentration with (spacing near4 (anode or cathode))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 10:23
9	BRS	L10	1976	(electroplate or electroplating or electroplated) with (concentration or (spacing near4 (anode or cathode)))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 10:24
10	BRS	L11	205	10 same thickness	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 10:25

	Type	L #	Hits	Search Text	DBs	Time Stamp
11	BRS	L12	164	11 and (@ad<20010719)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/29 10:25